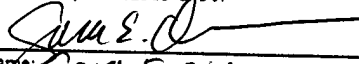


**COMPOSITIONS AND METHODS  
FOR REMOVING ETCH RESIDUE**

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**Abstract of the Disclosure**

A composition suitable for cleaning and methods of cleaning etch residue are provided. The composition includes at least one source of a fluoride ion and at least one organic solvent.

<p>"Express Mail" mailing label number: EV 201890269 US</p> <p>Date of Deposit: February <u>3</u>, 2004</p> <p>I hereby certify that this paper and/or fee is/are being deposited with the United States Postal Service "Express Mail Post Office to Addressee" service under 37 C.F.R. 1.10 on the date indicated above and is addressed to the Commissioner for Patents, Mail Stop Patent Application, P.O. Box 1450 Alexandria, VA 22313-1450.</p> <p> Name: <u>SAM E. OLSON</u></p>
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